# Masters for micro- and nanostructure replication by



Diplomvej 381 DK-2800 Kongens Lyngby Denmark <u>www.nilt.com</u> CVR: DK 29310203 Contact: Phone: +45 3111 1797 – Email: <u>contact@nilt.com</u>

# Background

- More than 8 years of experience in providing stamps to the imprint community
- 12 Full time employees
- More than 250 clients across the more than 30 countries
- Delivering products to meet technical and economical expectations from clients
- Striving to achieve the highest possible quality of stamps
- Working in state-of-the-art silicon processing cleanrooms, class 10/100, in Denmark and Sweden



# Added value by NILT

- Reduced prices if more than one stamp is ordered
- Repeat orders are subject to discounts
- High focus on delivered stamps fulfilling specs
- Close interaction with client already in design phase of the stamp
- High degree of production status to client





# **Stamps/molds by NILT**

### **Products**

- Silicon stamps
- Quartz stamps (including 65 Templates)
- Nickel shims
- Steel tools

### Technologies where master/stamps/molds are used

- Nanoimprint
- Hot embossing
- Roll-2-Roll printing
- Injection molding



# Silicon stamps/molds

Available sizes:

- Round: 2-inch, 4-inch round, 6-inch round, 8-inch round
- Any square format cut from wafers.

#### Stamp thickness

 In general the stamp thickness will follow the standard wafer thickness, i.e. 525 μm (2-inch and 4-inch), 675 μm (6-inch), and 725 μm (8-inch)

Anti-sticking and stamp cleaning

- We can apply anti-sticking coating (FDTS, 1H,1H,2H,2Hperflourodecyltrichlorosilane) onto all silicon stamps upon request
- Cleaning service is available upon request

#### Patterns

- We can prepare silicon stamps with features from below 20 nm
- Structures with lateral size of below 20 nm to 300 nm will be patterned with EBL
- Structures with lateral size of 300 nm to 2  $\mu\text{m}$  will be patterned with DUV
- Structures with lateral size larger than 2  $\mu m$  will be patterned with UVL

### Pattern depth/height

• The pattern depth/height depends on the lateral feature size

### Side wall

- Regular specification: 85-90°
- Other angles available upon request

Line Edge Roughness

Depends on etch depth and lateral and vertical dimensions



2-inch silicon NIL stamp with photonic crystal structures



## **Silicon stamps - examples**



Silicon grooves with widths from 153 nm to 26 nm



Pillars in fields with different lattice orientation



Cross section of 150 nm wide and 1  $\mu m$  high lines



Truncated pyramids



## **Silicon stamps - examples**



Shaping of silicon structures. Here pencil type protrusions



500 nm diameter holes in silicon



2  $\mu$ m wide and 2  $\mu$ m deep square holes



Polymer micro needles hot embossed from silicon master



## **Quartz stamps**

#### Materials

• Quartz, Fused silica, glass

#### Available sizes:

- Round: 2-inch, 4-inch round, 6-inch round, 8-inch round
- Any square format cut from wafers
- 65 mm X 65 mm x 6.35 mm (cut from 6026 mask blanks)

### Stamp thickness

• Stamp thickness from 200 μm

### Stamp cleaning

Cleaning service is available upon request

### Patterns

- We can prepare quartz stamps with features from 20 nm
- Structures with lateral size of 20 nm to 300 nm will be patterned with EBL
- Structures with lateral size of 300 nm to 2  $\mu m$  will be patterned with DUV
- Structures with lateral size larger than 2  $\mu m$  will be patterned with UVL

### Pattern depth/height

The pattern depth/height depends on the lateral feature size

### Side walls

Regular specification: 80-85°

### Line Edge Roughness

• Depends on etch depth and lateral and vertical dimensions



Image of 65 Template, cut from a 6025 Photomask. Pattern is located on central mesa



## **Quartz stamps - examples**



100 nm wide grooves



30 nm wide lines etched to a depth of 1  $\mu\text{m}$ 





 $50\,\mu\text{m}$  diameter concave lenses

# **Nickel shims**

Nickel shims for nanoimprint lithography, hot embossing, Roll-2-Roll printing and injection moulding.

Available sizes:

- Any shape/size cut from Ø140 mm diameter
- Up to 500 mm x 500 mm upon request and with certain limitation regarding structures

Shim thickness according to specification. Regular thickness is 300  $\mu$ m (thickness from tens of  $\mu$ m to several mm can be made)

Anti-sticking and stamp cleaning

- We can apply anti-sticking coating (FDTS, 1H,1H,2H,2Hperflourodecyltrichlorosilane) onto all silicon stamps upon request
- Cleaning service is available upon request

#### Patterns

• The Nickel shims are made from a resist pattern or a Silicon or Quartz master. Dimensions are available from 30 nm.

### Pattern depth/height

- The pattern depth/height depends on the lateral feature size
- Regular aspect ratio up to 1:2 as standard (higher upon request)

### Side walls

• Regular specification: 80-85°

### Line Edge Roughness

Depends on etch depth and lateral and vertical dimensions

Various types of nickel (different hardness) can be provided upon request



- Developed technology for shim fabrication for microfluidics and lab-on-a-chip purposes.
- Combining micro- and nanostructures
- Several layers
- Contact NILT to learn more



## **Nickel shims - examples**



Moth-eye structures with 2  $\mu$ m pitch



Moth-eye structures with 2 µm pitch (top view)



Confocal microscopy image of a dual layer Ni shim with 20  $\mu m$  depth and 1  $\mu m$  tall structures



Ni shim for  $\mu\mbox{-}fluidic \mbox{-}applications.$  Structures are 30  $\mu\mbox{m}$  tall.



## **Nickel shims - examples**



Nickel shim with isolated mesas, each having diffraction grating on top.



Nickel shim ready for replication by injection moulding.

Pattern consist of holes placed in hexagonal lattice, having diameter of 500 nm, period of 750 nm and depth of 825 nm.





### NICKEL SHIM WITH 500 NM DIAMETER HOLES



Nickel shim ready for replication by injection moulding.

Pattern consist of holes placed in hexagonal lattice, having diameter of 500 nm, period of 750 nm and depth of 825 nm.



# **Advanced processing by NILT**

### Multilevel structures

- Alignment accuracy between layers
  - <30 nm with EBL</p>
  - <100 nm with DUV</p>
  - <4  $\mu$ m with UVL

### **3D structures**

 Arbitrary continous functions f(x,y) can be made with 3D EBL and transferred both to Silicon and Quartz. However due to scattering effects there is a limit to how sharp transitions between different heights can be achieved.

### Micro Lenses

- Concave lens shapes can be done in quartz
- SAG < 2D where D=diameter of lens





## **Steel tools**

Nanopatterned plastics produced by injection moulding

We are developing technology for patterning injection molding steel tools with micro- and nanostructures. The patterns are made in a hard coating on top of the steel which ensures long life time of the structures.

The developments are on-going and is mainly performed in the two projects NanoPlast (Danish National Advanced Technology Foundation) and Plast-4-Future (EU FP7). We gain new results on a daily basis, so you are welcome to contact us to discuss current and future solutions relevant to you.

Our focus is to create the most advanced high precision injection moulding tools in the market.

Target is to provide our clients with the capability to make very fine structures in platics directly in the injection moulding process AND to provide injection moulding steel tools with engineered surfaces to provide specific functionalies in the plastic products.

We are currently studying the following applicaton areas:

- Decoration (including colours)
- Anti-counterfeiting
- Labelling
- Water/substance repelling
- Anti-reflection
- Anti-fog/ice
- Anti-biofouling/bacteria





Nanopatterned steel tool



Artist impression of self-cleaning and colour properties that can be created through injection moulding in polymer surfaces. Functionalities are inspired from nature, but the structures are designed for manufacturing.



## **Contact NILT**

NIL Technology ApS (Headquarters) Diplomvej 381 Kongens Lyngby Denmark Phone: +45 3171 1797 <u>contact@nilt.com</u>

NILT Sweden Filial (Branch) Stena Center 1B 412 92 Gothenburg Sweden Phone: +46 70-857 96 69 <u>contact@nilt.com</u>



### Agents

### Japan

HTL Co Japan Ltd Tachikawa City (Tokyo), Japan <u>www.htlco.co.jp</u> Masashi Tsutsui m.tsutsui@htl.co.jp

### Singapore

Gaia Science Pte Ltd Singapore, Singapore www.gaiascience.com.sg Tony Lee tonylee@gaiascience.com.sg

### India

HTL Co Ltd India Bangalore, India <u>www.htl.co.jp</u> Sanjay Acharya: <u>s.acharya@htlco.co.jp</u>



### **Contact NILT**

NIL Technology ApS Diplomvej 381 Kongens Lyngby Denmark Phone: +45 3171 9036 Email: <u>contact@nilt.com</u>

Contact persons: Theodor Nielsen, founder, CEO Phone: +45 3171 9036 Email: <u>theo@nilt.com</u>

Brian Bilenberg, founder, CTO Phone: +45 3171 9037 Email: <u>bb@nilt.com</u>

Niklas Hansson, Director of Sales Phone: +46 70 857 9669 Email: <u>nh@nilt.com</u>



